

(maximum) x 200  $\mu$ m (minimum). The foil is manufactured by electroforming in one piece and is open at its base. By virtue of its shape, the foil has an arcuate longitudinal centre line, like a banana, and may be a sector of a torroid.--

Replace the paragraph beginning at page 10, line 32 with the following:

--Figs. 10 to 22 show a modified embodiment of the invention including a straight shaving foil 100 having a parabolic shaving surface and closed elliptic end cheeks 101, 102. Fig. 11 shows a longitudinal sectional view taken along line A - A of Fig. 10. The view of Fig. 11 shows the undercutter 181, which is constructed in a substantially conventional way. Fig. 12 is a cross-section taken along line B - B of Fig. 11.--

Replace the paragraph beginning at page 22, line 19, with the following:

--5.2 As shown in Fig. 32, develop the mandrel pattern in "Developer"<sup>TM</sup> 41 while stirring with a stirrer 42 and at 20-50°C, preferably 26°C until the aperture pattern is just visible; note the time taken and continue the immersion for the same period.--

Replace the paragraph beginning at page 23, line 1, with the following:

--Fig. 27 shows the mask 242 with its foil aperture pattern 244. Fig. 28 shows the polished mandrel 261 coated with photoresist ready to receive the mask 242.--

In the claims:

Please amend claim 22 as follows:

-- 22. (Twice Amended) A method of producing an electroformed shaving cutter comprising:

- a) providing a substrate that has an electrically-conductive surface;
- b) applying a coating of electrophoretic photoresist to the electrically conductive surface by passing an electrical current therethrough;
- c) exposing the photoresist to a suitable source of electromagnetic radiation through a mask that is shaped to conform to that of said electrically conductive surface of said substrate;

d) developing the photoresist; and

e) electrodepositing a metallic layer onto conductive surface regions of the substrate not coated with the photoresist.--

---

Please add claim 41.

---

41 -- 41. (New) A method according to claim 22, wherein the step of applying further comprises applying the electrophoretic photoresist as a liquid. --

---

In the drawings:

Please substitute the attached sheets of drawings containing modified Figs. 11, 12, 18, 27, and 32 for the corresponding sheets of drawings presenting those figures as originally filed.